

JAYPEE UNIVERSITY OF INFORMATION TECHNOLOGY, WAKNAGHAT

T-2 EXAMINATION- OCTOBER 2018

Ph.D I Semester

Dr. Harsh

COURSE CODE: 13P1WPH113

MAX. MARKS: 25

COURSE NAME: ADVANCED MATERIALS SCIENCE

COURSE CREDITS: 03

MAX. TIME: 1.5 Hrs

Note: All questions are compulsory. Carrying of mobile phone during examinations will be treated as case of unfair means.

Q1. Answer briefly:

[1×5=5-marks]

- a. What is the cause of strain in material?
- b. Obtain the edge length ratio (c/a) in a hexagonal close packed lattice?
- c. How spontaneity of a chemical reaction is determined?
- d. What is the basis of Arrhenius rate equation?
- e. What is the cause of bonding in solids?

Q2. What is homogeneous nucleation? Elaborate with the concept of supersaturation the nucleation and growth mechanism in zero dimensional nanoparticles.

[5-marks]

Q3. Write short notes:

[2.5×2=5-marks]

- a. Parametric control in thin film growth by sol-gel technique.
- b. Capacitance-Voltage (C-V) measurements.

Q4. (i) How to use physical vapor deposition technique to generate nanostructure on a substrate? (ii) Obtain an expression for the carrier concentration in terms of built in voltage in a p-n junction.

[2.5×2=5-marks]

Q5. In BJT n-p-n or p-n-p devices, explain the significant physical characteristic of the base. How will you fabricate a silicon n-p-n transistor?

[5-marks]